

IN THE CLAIMS

Please amend Claim 13 as shown in marked-up form:

HMC

1. (Previously Presented) A device for the inspection of one or more a rotating surface (8) of a wafer (13), which device includes at least one light source (1), and a beam splitter (4) for splitting a light beam (2) that is emitted by said source into at least one reference beam (6) that is applied to a detector (16) and at least one measuring beam (5) that is applied to the surface (surfaces), the at least one measuring beam (5) containing at least one component in the direction of movement (U) of the relevant surface (8) or in the opposite direction, and the light (15) that is reflected by the surface (8) having, at least upon detection of a defect (14) on the surface (8), a frequency (v') that has been shifted relative to the at least one measuring beam (5) and that the at least one reference beam (6) can be superposed thereon, characterized in that the device includes an evaluation unit (29) for determining the velocity (v) of a defect (14) on the surface (8) from the shifted frequency (v') and from this velocity the position of the defect on the surface (8).
2. (Original) A device as claimed in claim 1, characterized in that the detector (16) has exactly one entrance window that is